

MEXT (Ministry of Education, Culture, Sports, Science and Technology) Knowledge Cluster Initiative (The Second Stage) ~ Tokai Region Nanotechnology Manufacturing Cluster ~





Third International Symposium on Advanced Plasma Science and its Applications for Nitrides and Nanomaterials

March 6-9, 2011

Nagoya Institute of Technology, Nagoya, Japan

Organizing Committee

Chairperson: Masaru Hori, Plasma Nanotechnology Research Center, Nagoya University Vice-Chairperson: Hideki Masuda, Nagoya Institute of Technology Hiroshi Amano, Meijo University Keiji Nakamura, Chubu University

The ISPlasma is held as part of the Expansion Program of the Second Stage Knowledge Cluster Initiative (Tokai Region Nanotechnology Manufacturing Cluster) to establish an Advanced Plasma Nanotechnology Science Research Foundation in the Tokai region. In order to both accelerate the international collaboration and reinforce the personal network, this symposium is held continually every year.

SCOPE

◆Plasma Science and Technology

(Plasma Measuring Technology/Simulation/Etching Process/CVD Process/Solar Cells/ Flexible Electronics/Plasma Applications)

Nitride

(Crystal Growth/MBE Growth/Plasma Processing/Electronic Devices/White LEDs/UV LEDs) Nanomaterials

(Nanocarbon Materials/Solar Cells/Surface Modification/Surface Functionalization/ Composite Materials/Functionally Grade Materials/Nanoparticles)

◆Integration Technology of Plasma Science, Nitrides and Nanomaterials

◆Industry -Academia-Government Collaboration

OABSTRACT SUBMISSION

Each author is requested to submit a one-page abstract written in English. The page for the abstract submission will be made on our website in April, 2010. http://www.isplasma.jp/ Abstract Deadline: November 8, 2010

OSPECIAL ISSUE

The selected papers are planned to be published in a special issue of a scientific journal.

Contact

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